SUBSTRATE SUPPORT, ELECTROSTATIC CHUCK, PLASMA PROCESSING APPARATUS, AND METHOD FOR MANUFACTURING ELECTROSTATIC CHUCK

Abstract

To provide a technique capable of quickly controlling a temperature of a substrate or a substrate support. The substrate support includes a base including a flow path through which a temperature-controlled medium flows; a support placed on the base, the support including a front surface that supports a substrate and a back surface; and a heat flux sensor placed on the back surface of the support.

Fig. 4